Apparatus and method for cleaning a sawn wafer block

Abstract

An apparatus for cleaning a sawn wafer block (40) comprises a cleaning basin (10), a fixture (50, 52) for holding a sawn wafer block (40) in the cleaning basin (10) such that, when cleaning liquid (34) is present in the cleaning basin (10), at least a portion of the wafer block (40) comprising sawn gaps is disposed in the cleaning liquid, at least one outlet port (18) in a bottom region (16) of the cleaning basin (10), and closure means (20, 22) for the outlet port (18), by means of which the outlet port (18) may be opened and closed. The closure means (20, 22), the outlet port (18) and the bottom region of the cleaning basin are configured such that, by opening the closure means (20, 22), the cleaning liquid is drainable so fast from at least the area of the cleaning basin (10) having the wafer block disposed therein that contaminants are removable from the sawn gaps due to a suction effect of the cleaning liquid.

Fig. 1